

FORM PTO-1449 (Modified)		Attorney Docket No.: 020185-000110US		Application No.: 09/911,763	
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)		Applicant: Farid Askarieh		OCT 04 2001 FILING DATE RECEIVED U.S. PATENT AND TRADEMARK OFFICE OCT 04 2001 CANCELLATION	
Reference Designation		U.S. PATENT DOCUMENTS			
Examiner Initial	Document No.	Date	Name	Class	Sub-class
0001	4,818,873	04/1989	Herriot	250	310
0002	5,644,512	07/1997	Chernoff et al.	364	571.02
FOREIGN PATENT DOCUMENTS					
	Document No.	Date	Country	Class	Sub-class
					Translation (Yes/No)
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)					
0003	Ronald Dixson et al, National Institute of Standards and Technology, "Dimensional Metrology with the NIST Calibrated Atomic Force Microscope", Proceedings of SPIE, Volume 3677, pp. 20-34, 1999				
0004	S.R. Dooley et al, "Comparison of discrete subsample time delay estimation methods applied to narrowband signals", Measurement Science and Technology, Volume 9, pp. 1400-1408, 1998				
0005	Scott C. Douglas, "A Frequency Domain Subpixel Position Estimation Algorithm for Overlay Measurement", Proceedings of SPIE, Volume 1926, pp. 402-405, 1993				
0006	D. M. Holburn et al, "A Pattern Recognition Technique Using Sequence of Marks for Registration in Electron Beam Lithography", Journal of Vacuum Science and Technology, Volume 19(4), pp. 1229-1233, 1981				
0007	Fumio Mizuno et al, "Evaluation of the long-term stability of critical-dimension measurement scanning electron microscopes using a calibration standard", Journal of Vacuum Science and Technology B, Volume 15(6), pp. 2177-2190, 1997				
0008	Anatoly Shchemelinin et al, "Basic Challenges of Optical Overlay Measurement", Proceedings of SPIE, Volume 3050, pp. 425-431, 1997				
0009	J.S. Villarubia et al, National Institute of Standards and Technology, "Intercomparison of SEM, AFM, and Electrical Linewidths", Proceedings of SPIE, Volume 3677, pp. 587-597, 1999				
0010	Alexander I. Zaslavsky, "Overlay Measurement and Edge Detection Methods", Proceedings of SPIE, Volume 3050, pp. 418-424, 1997				
0011	N. F. Zhang et al, National Institute of Standards and Technology, "A New Algorithm for the Measurement of Pitch in Metrology Instruments", Proceedings of SPIE, Volume 2725, pp. 147-158, 1996				
EXAMINER	DATE CONSIDERED		4-27-04 OCT 9 2001 2000 MAIL ROOM		

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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